IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Takayuki SHIMAMUNE et al.   Conf. 2298

Application No. 10/527,801   PCT/DO/EO
   (PCT/JP/03/11656)

Filed March 14, 2005

PROCESS FOR PRODUCING HIGH-PURITY
SILICON AND APPARATUS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents   November 14, 2005
P.O. Box 1450
Alexandria, VA   22313-1450

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, the accompanying document, a copy of which is attached to this statement, is made of record on the enclosed Form PTO-1449.

A concise explanation of the relevance of this item is that this reference (JP 2003-342016) was cited in the corresponding International application but erroneously identified in the search report as 2003-**2**42016.

Respectfully submitted,

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)	Attorney Docket No.: **8038-1062**	Application No.: **10/527,801**
	Applicant: **Takayuki SHIMAMUNE et al.**	
	Filing Date: **March 14, 2005**	Group Art Unit:

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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing date (if appropriate)

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
	2003-342016 (with English abstract)	12/3/03	Japan				x

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER:	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* Abstract provided for the Examiner's convenience

Y&T May 27, 2005